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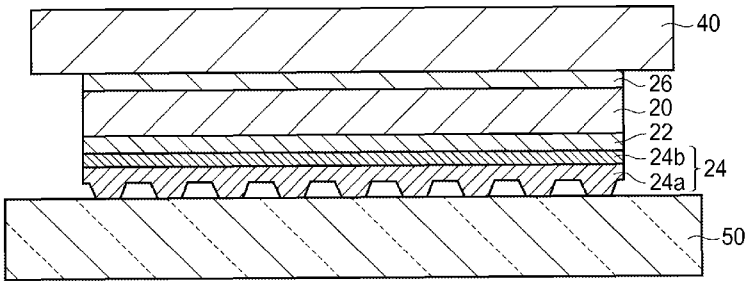

FIG. 4

(57) Abstract: A structural member for polishing including a supporting member, a polishing material, and an adhesive agent layer bonding these together. The adhesive agent layer includes a polymer of monomers including from 58 to 85 wt% of a first monomer, from 2 to 7 wt% of a second monomer, and from 10 to 40 wt% of a third monomer. The first monomer is an alkyl (meth)acrylate having an alkyl group with carbon counts from 8 to 18 carbon atoms and provides a homopolymer with a glass transition temperature of 0°C or less. The second monomer is a polar monomer that provides a homopolymer with a glass transition temperature of 50°C or greater. The third monomer is an alkyl (meth)acrylate having an alkyl group with carbon counts from 4 to 18 carbon atoms or an aralkyl group having carbon counts from 7 to 18 carbon atoms and provides a homopolymer with a glass transition temperature of 10°C or greater.

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